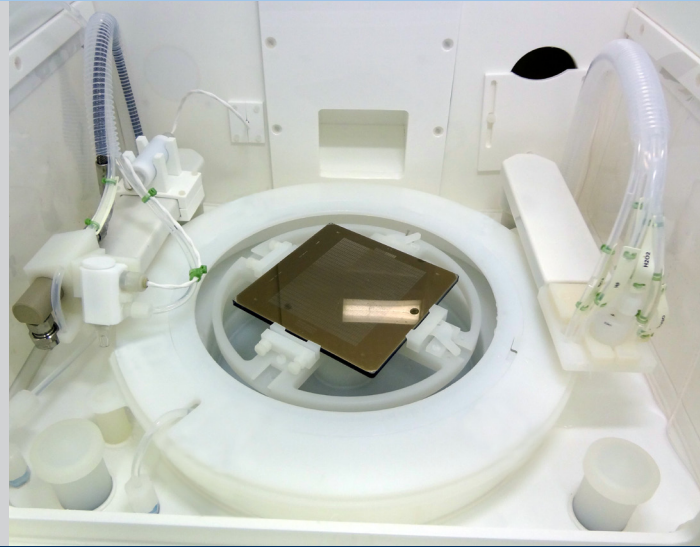


WE ARE **THE**  
**PARTNER**  
FOR CUSTOMIZED WET PROCESS  
**EQUIPMENT**

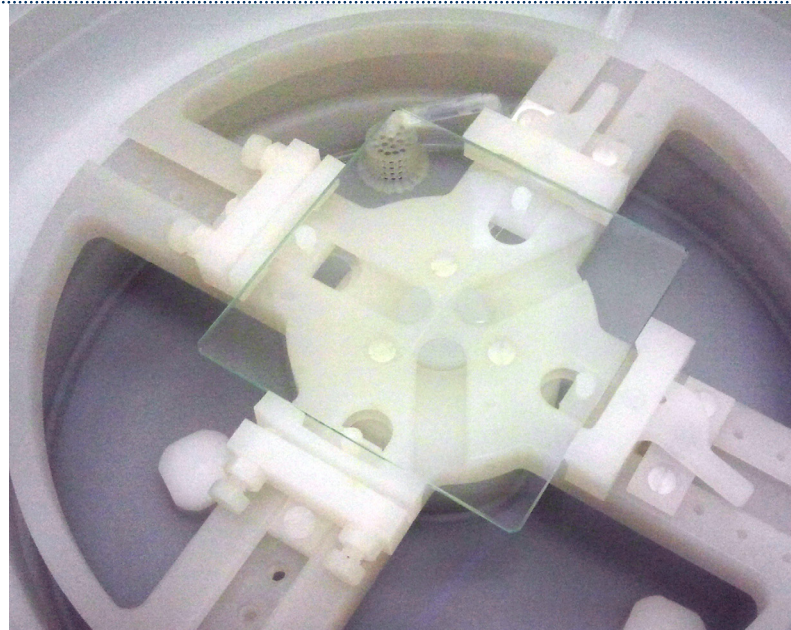
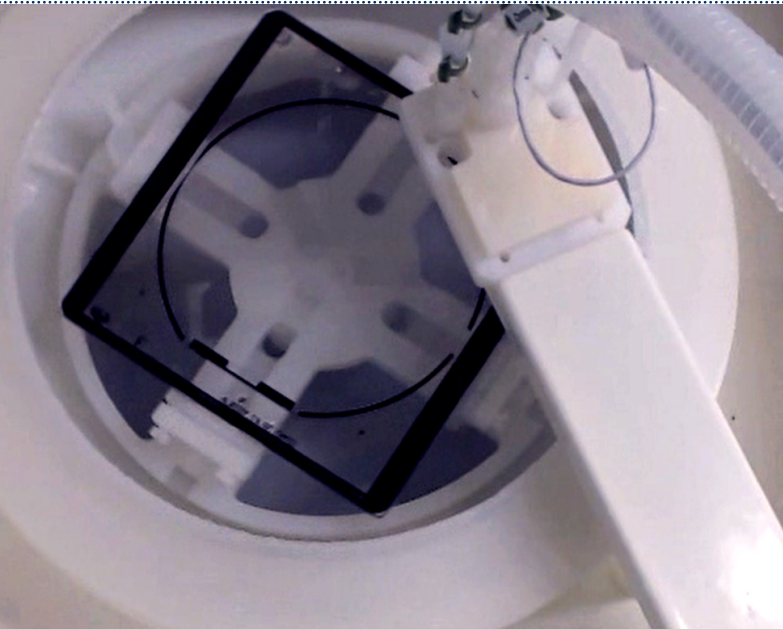


## Spin *Mask*

Mask processor from SEMIPARTS. Our proved tool for mask cleaning and etching processes.

## BENEFITS

- Suitable for masks and other substrates
- Piranha process used to clean organic residues off substrates
- SC1 base peroxide mixture removes organic residues and is also very effective in removing particles from the surface
- Low chemical and water consumption
- High safety levels for chemical usage
- Easy to change mask/wafer size
- State of the art software with multi touch functions
- Optimized footprint
- Easy to configure and upgradeable



## APPLICATIONS

The **SpinMask** is designed for processes like:

- Photo mask cleaning
- Photo mask etching
- Photo mask resist strip

## OPTIONS

- Piranha Process
- Standard clean SC1
- Single side brush
- High pressure cleaning
- CO<sub>2</sub> ionisation unit
- Mini chemical dispense and mixture system
- SECS GEM Interface
- Efficient chuck and bowl cleaning system

TECHNICAL DATA	SpinMask 200	SpinMask 300
Other substrates	on request	on request
Mask size	up to 7"	up to 9"
Mask cleaning	yes	yes
Mask etching	yes	yes
Combined chucks	yes	yes
Dimensions (W x D x H)	600 x 1300 x 2000 mm	600 x 1300 x 2000 mm